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**VE320 – Summer 2022**

**Introduction to Semiconductor Devices**

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**Chapter 5 Carrier Transport Phenomena**



# Outline

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## 5.1 Carrier drift

## 5.2 Carrier diffusion

## 5.3 Graded impurity distribution

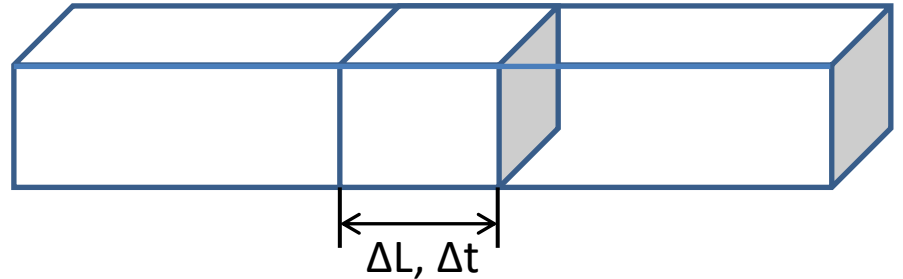
# 5.1 Carrier drift

## Drift current density

### Drift current

$$I_{drf} = \frac{\Delta Q}{\Delta t} = \frac{qp_0 A_c \Delta L}{\Delta t} = qp_0 A_c v_d$$

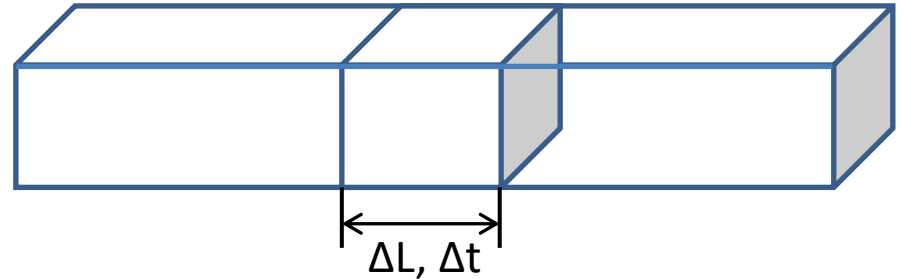
$$I_{drf} = \frac{\Delta Q}{\Delta t} = \frac{qp_0 \Delta L A_c}{\Delta t} = \overset{\rho: \text{charge density}}{p_0 q} v_d A_c$$



*for p type semiconductor,  $p_0 \gg n_0$*

# 5.1 Carrier drift (current in an ideal case)

## Drift current density



for p type semiconductor,  $p_0 \gg n_0$

## Drift current

$$I_{drf} = \frac{\Delta Q}{\Delta t} = \frac{qp_0 A_c \Delta L}{\Delta t} = qp_0 A_c v_d$$

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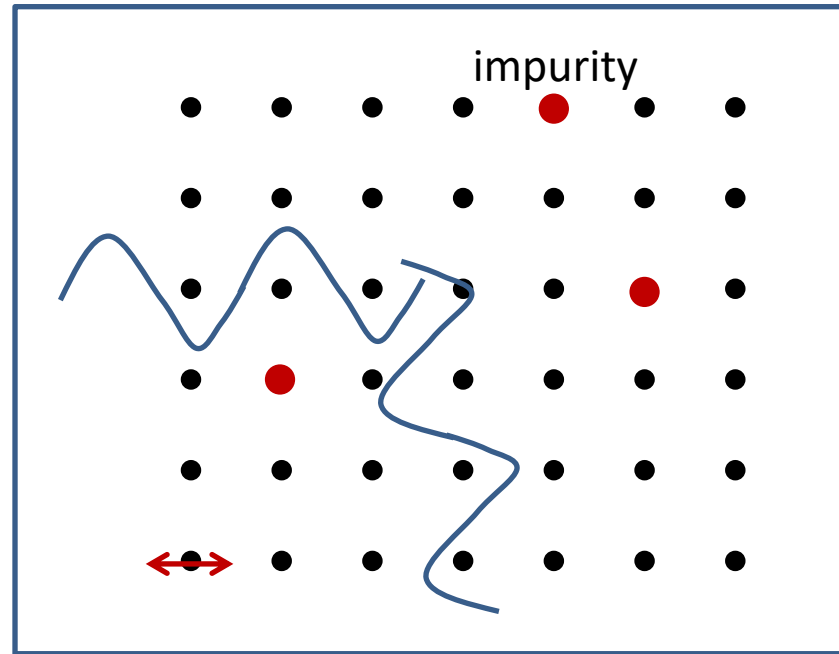
$$L = \frac{1}{2} a t^2 \rightarrow t = \sqrt{2L/a}$$

$$\rightarrow v_d = at = \sqrt{2La} = \sqrt{2LqE/m_{cp}^*} \left. \begin{array}{l} E = V/L \end{array} \right\} \rightarrow v_d = \sqrt{2qV/m_{cp}^*}$$

$$\therefore I_{drf} = qp_0 \sqrt{2qV/m_{cp}^*} A_c$$

However, Ohm's Law tells us:  $I = \sigma \cdot V$

## 5.1 Carrier drift (phonons and scatterings)



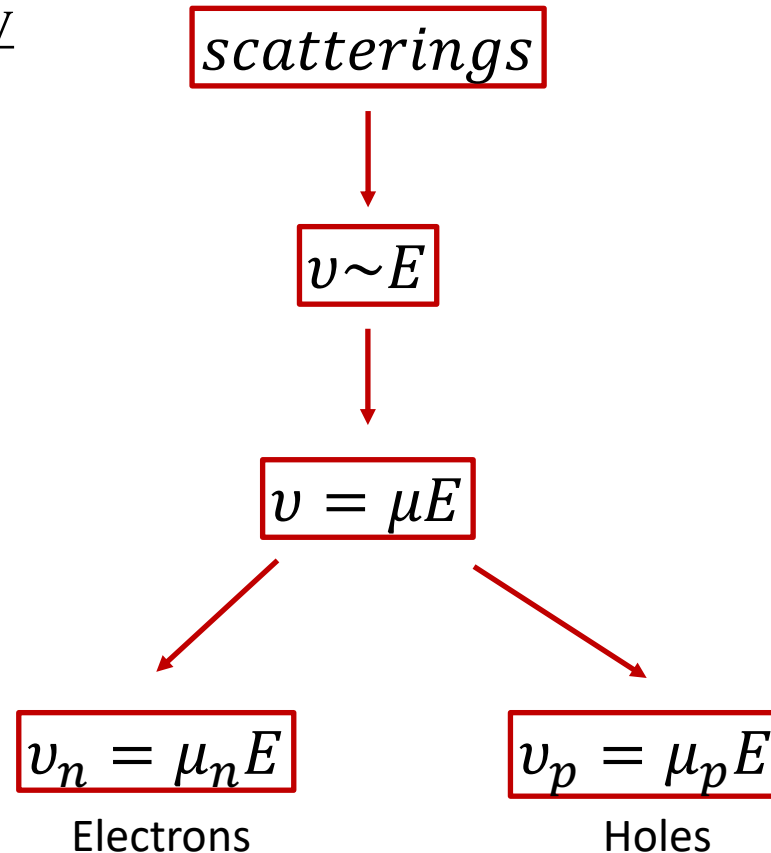
Thermal vibrations of lattice are phonons

**Scatterings** include:

- Electrons scatter with phonons
- Electrons scatter with Impurities

# 5.1 Carrier drift

## Drift current density



$$I_{drf} = \frac{\Delta Q}{\Delta t} = \frac{qp_0 A_c \Delta L}{\Delta t} = qp_0 A_c v = qp_0 A_c \mu_p E = qp_0 A_c \mu_p \frac{V}{L} = \sigma \cdot V$$

# 5.1 Carrier drift

## Drift current density

Hole drift current

$$J_{p|drf} = qp_0\mu_p E$$

Electron drift current

$$J_{n|drf} = qn_0\mu_n E$$

Both electrons and holes contribute to current:

$$J_{drf} = q(p_0\mu_p + n_0\mu_n)E$$

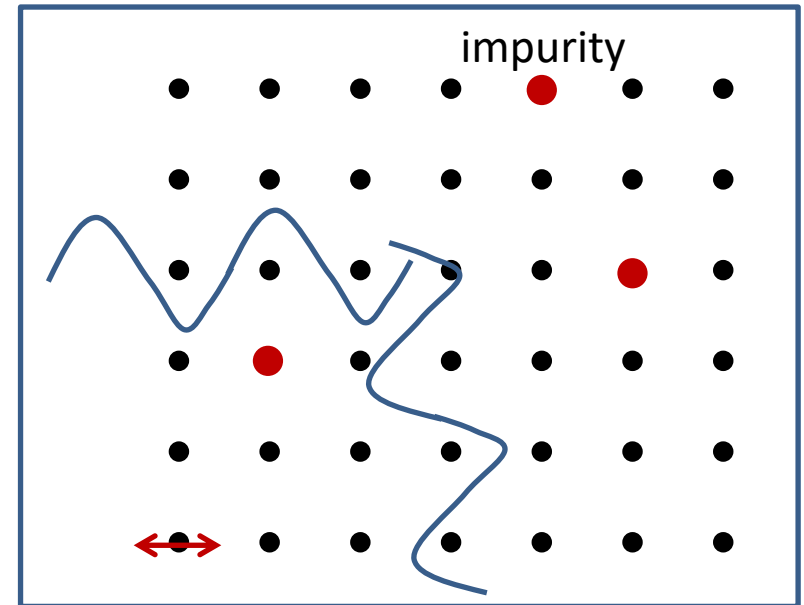
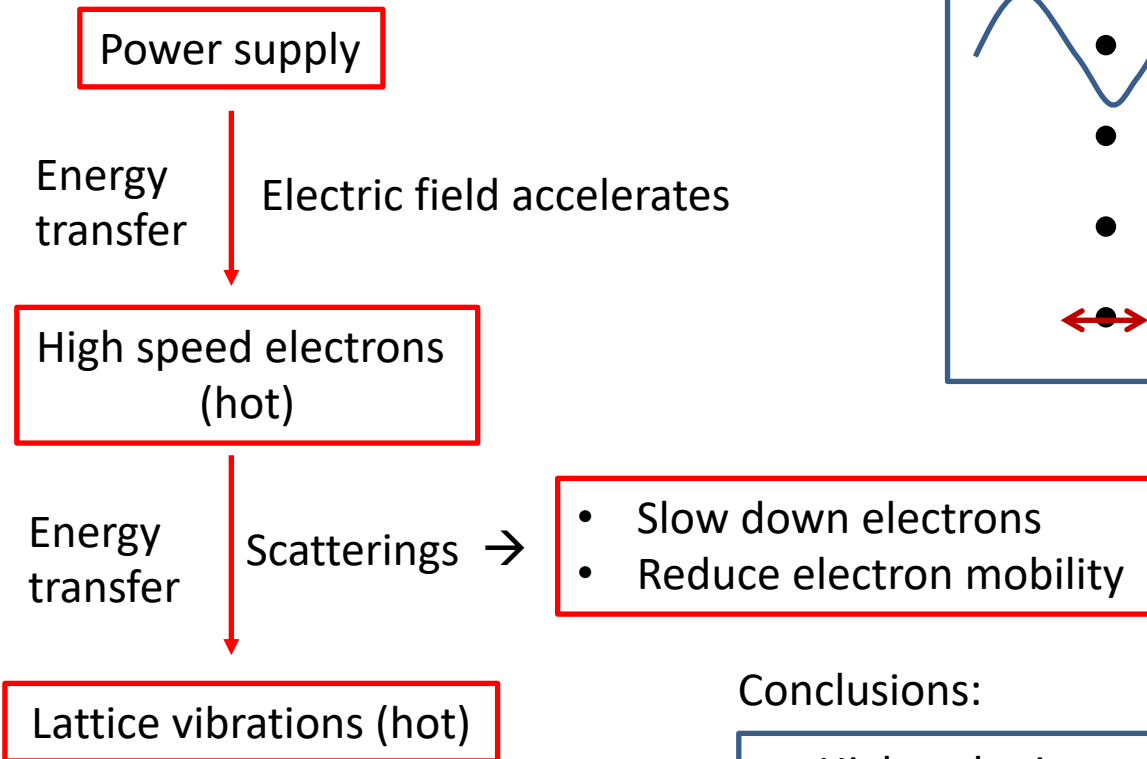
**Table 5.1** | Typical mobility values at  $T = 300$  K and low doping concentrations

	$\mu_n$ (cm <sup>2</sup> /V-s)	$\mu_p$ (cm <sup>2</sup> /V-s)
Silicon	1350	480
Gallium arsenide	8500	400
Germanium	3900	1900

# 5.1 Carrier drift

## Mobility effect

Why are resistors heated up by current?



Conclusions:

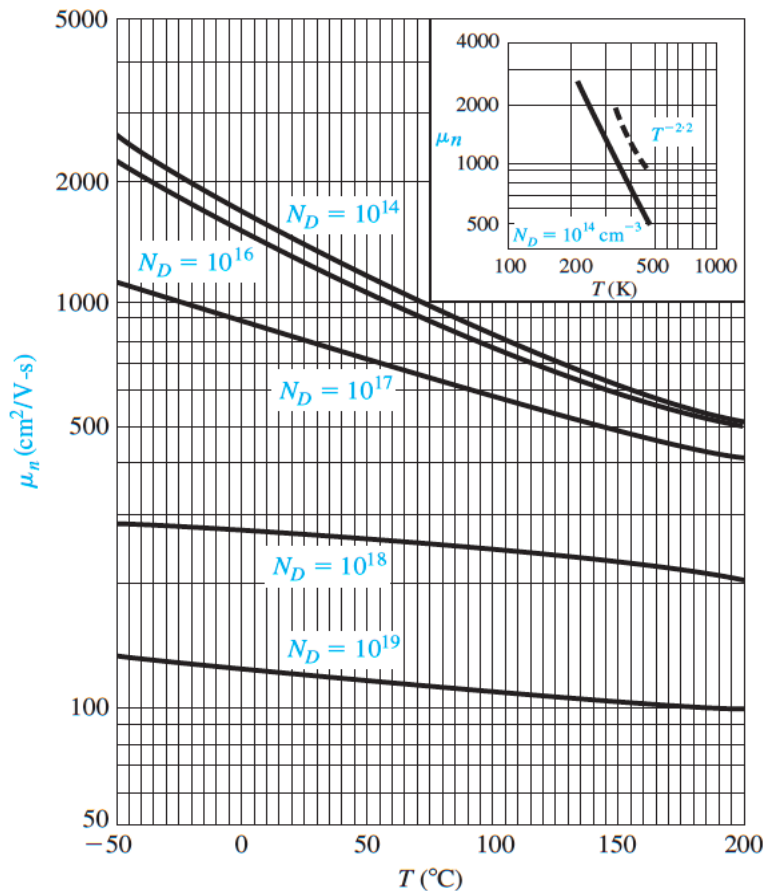
- Higher doping concentration → lower mobility
- Higher Temperature → lower mobility



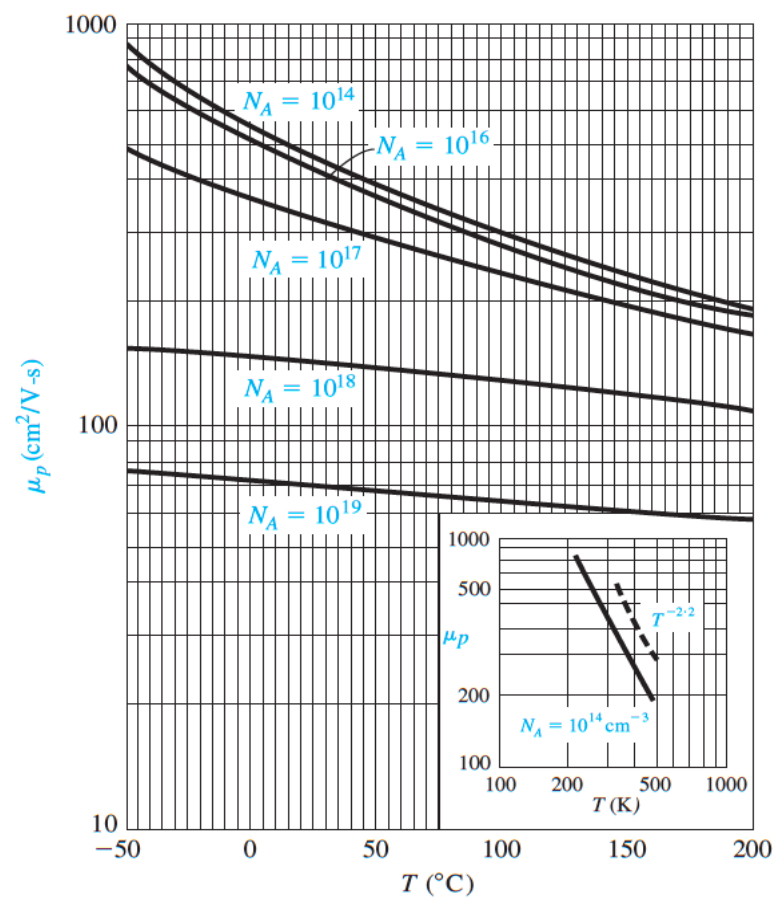
# 5.1 Carrier drift

Mobility effect: higher T and higher doping  $\rightarrow$  lower mobility

Electron mobility in n-type doping



Hole mobility in p-type doping



# 5.1 Carrier drift

## Conductivity

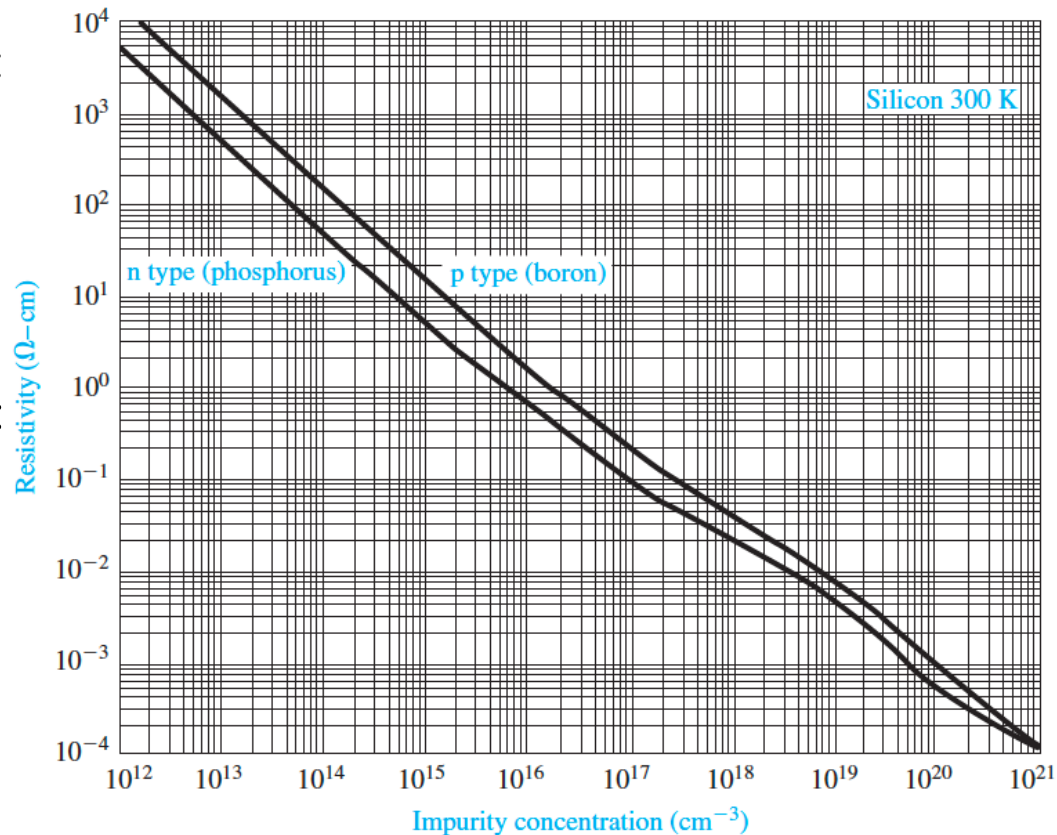
$$J_{drf} = q(p_0\mu_p + n_0\mu_n)E \Rightarrow \rho = \frac{1}{\sigma} = \frac{1}{q(\mu_n n + \mu_p p)}$$

For n-type doped semiconductor:

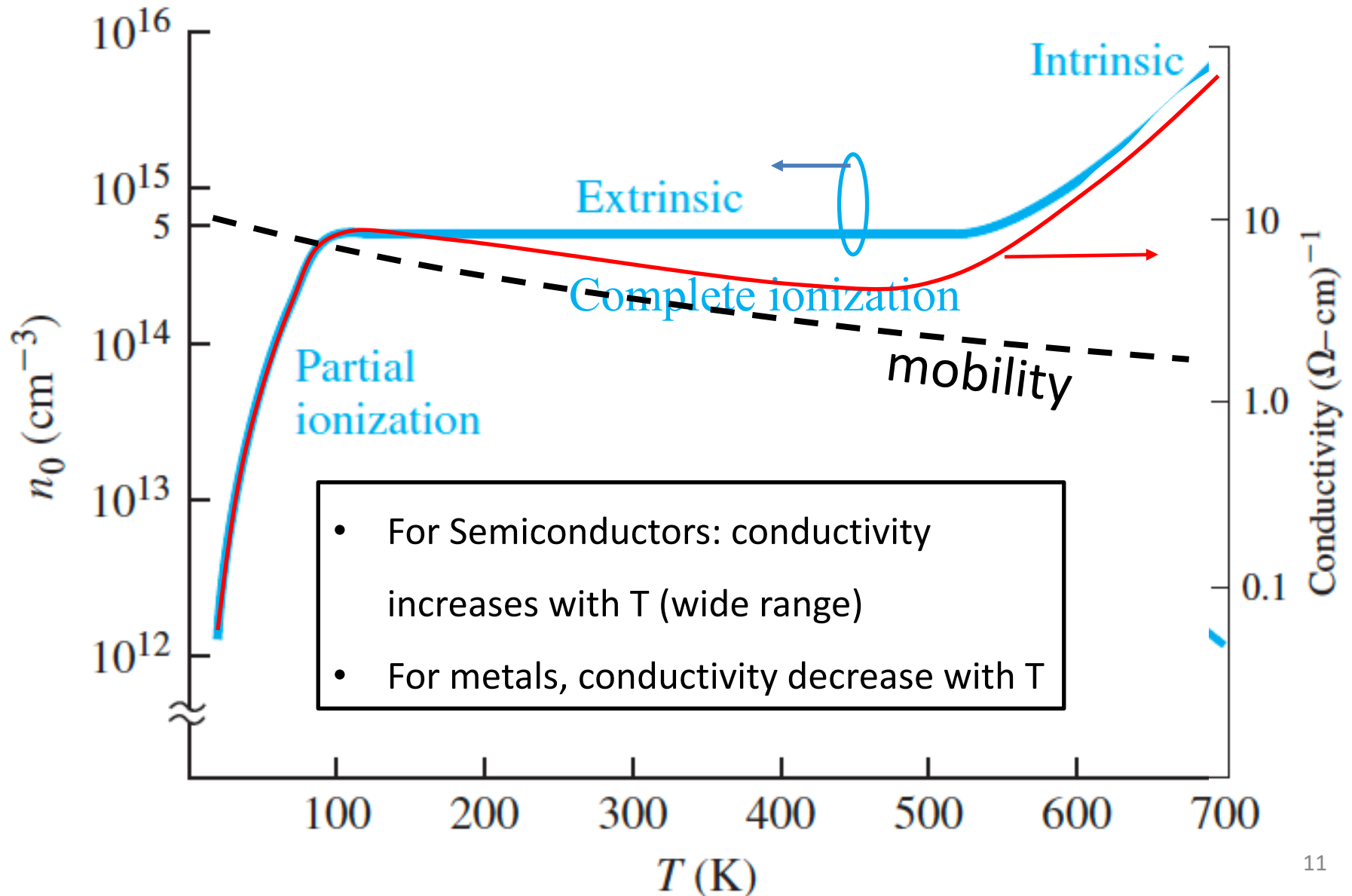
$$\rho = \frac{1}{\sigma} = \frac{1}{q\mu_n n} = \frac{1}{q\mu_n N_d}$$

For p-type doped semiconductor:

$$\rho = \frac{1}{\sigma} = \frac{1}{q\mu_p p} = \frac{1}{q\mu_p N_a}$$



## 5.1 Carrier drift (conductivity dependent on temperature)



# 5.1 Carrier drift

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## Velocity saturation

$$\frac{1}{2}mv_{th}^2 = \frac{3}{2}kT = 0.03885eV \text{ (300K)}$$

$$\Rightarrow \text{thermal velocity } v_{th} \approx 10^7 \text{ cm/s}$$

$$\text{Drift velocity } v_d = \mu_n E$$

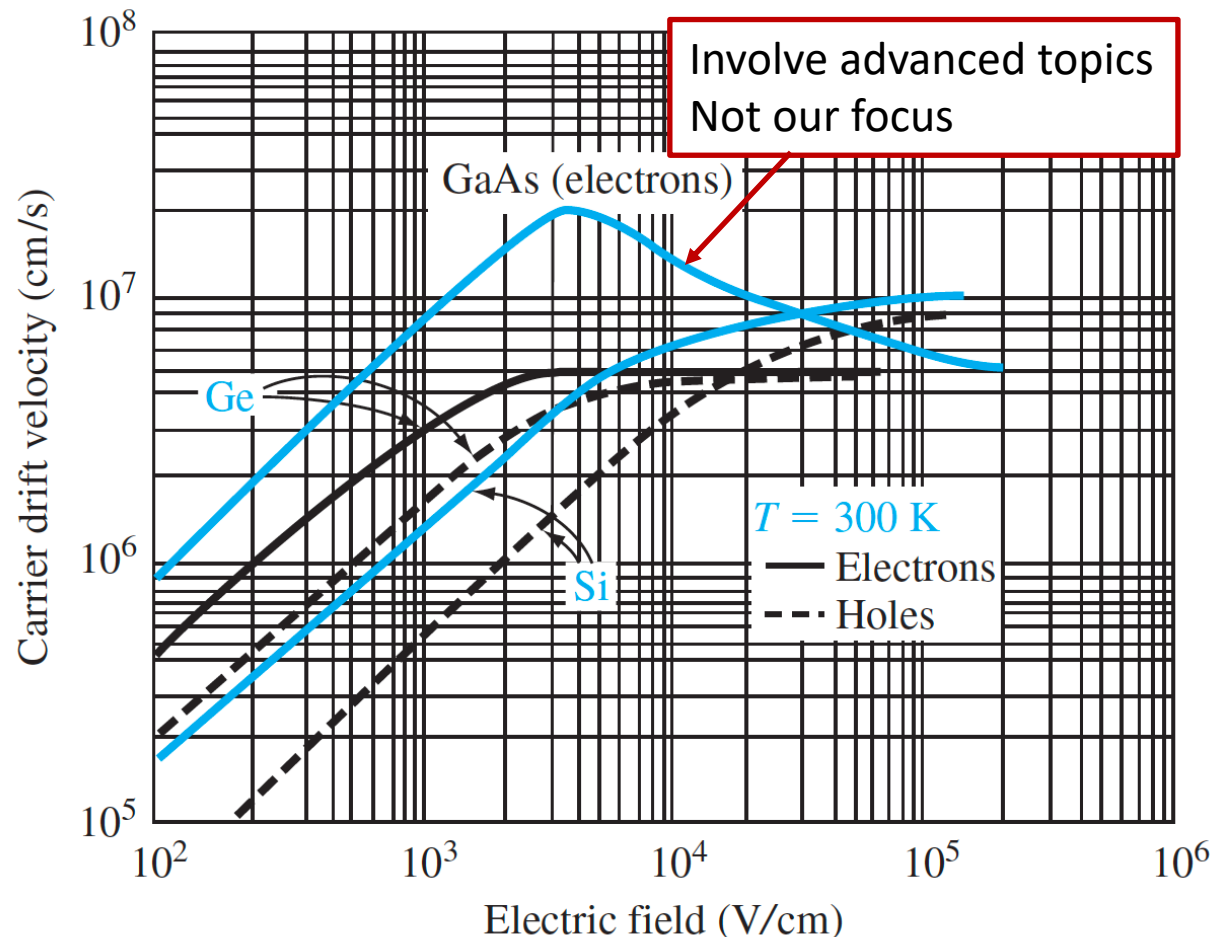
$$\Rightarrow E = \frac{v_d}{\mu_n} = \frac{10^7 \text{ cm/s}}{1350 \text{ cm}^2/(Vs)} = 7 \times 10^3 \text{ V/cm}$$

# 5.1 Carrier drift

## Velocity saturation

$$v_d \rightarrow v_{th}$$

- Electric field is heating up electrons
- Electrons transfer energy to lattice to reach thermal equilibrium



$$v_n = \frac{v_s}{\left[1 + \left(\frac{E_{on}}{E}\right)^2\right]^{1/2}}$$

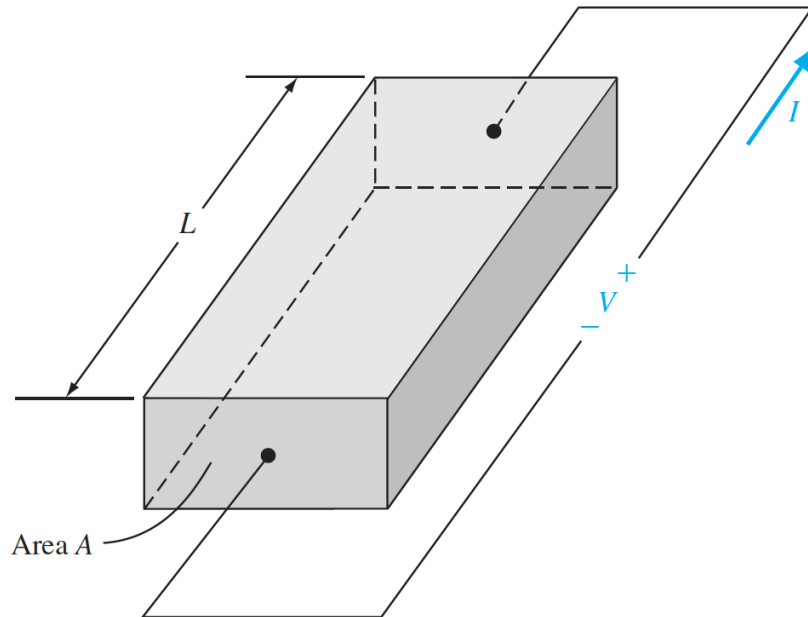
$$v_p = \frac{v_s}{\left[1 + \left(\frac{E_{op}}{E}\right)^2\right]^{1/2}}$$

Probably a typo in textbook

# Check your understanding

## Problem Example #1

A bar of p-type silicon at 300K in the figure below has a cross-sectional area  $A = 10^{-6} \text{ cm}^2$  and a length  $L = 1.2 \times 10^{-3} \text{ cm}$ . For an applied voltage of 5V, a current of 2mA is required. What is the required (a) resistance, (b) resistivity, and (c) impurity doping concentration? (d) What is the resulting hole mobility?



# Outline

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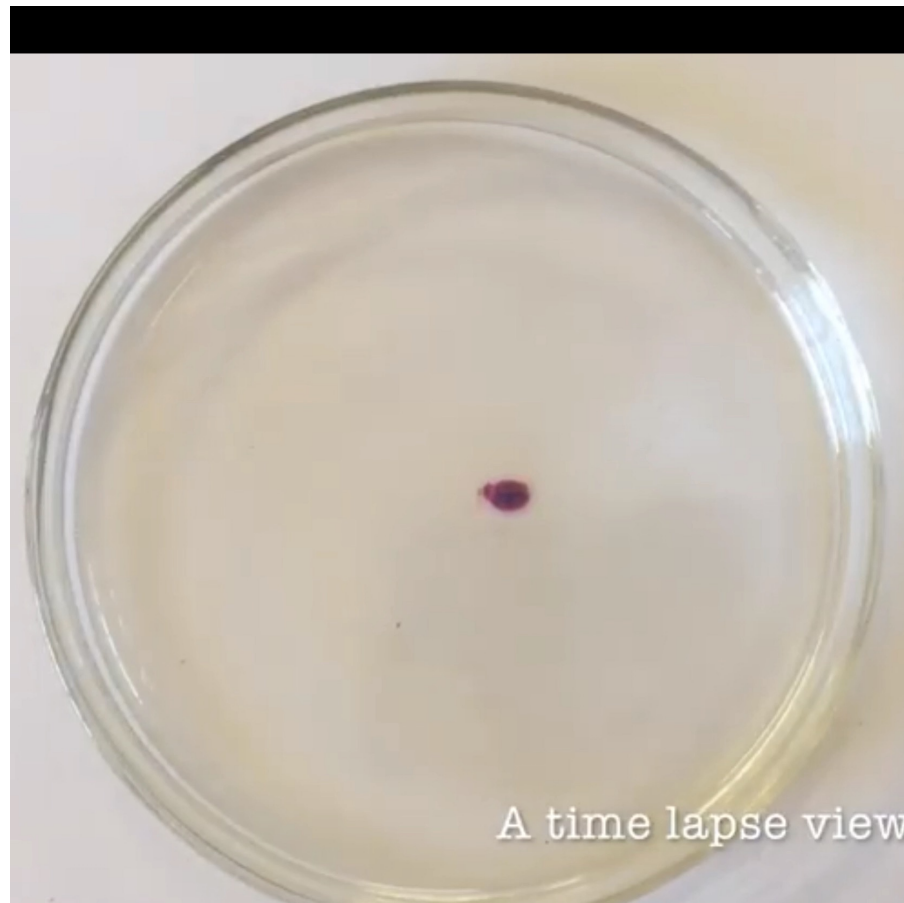
5.1 Carrier drift

**5.2 Carrier diffusion**

5.3 Graded impurity distribution

## 5.2 Carrier diffusion

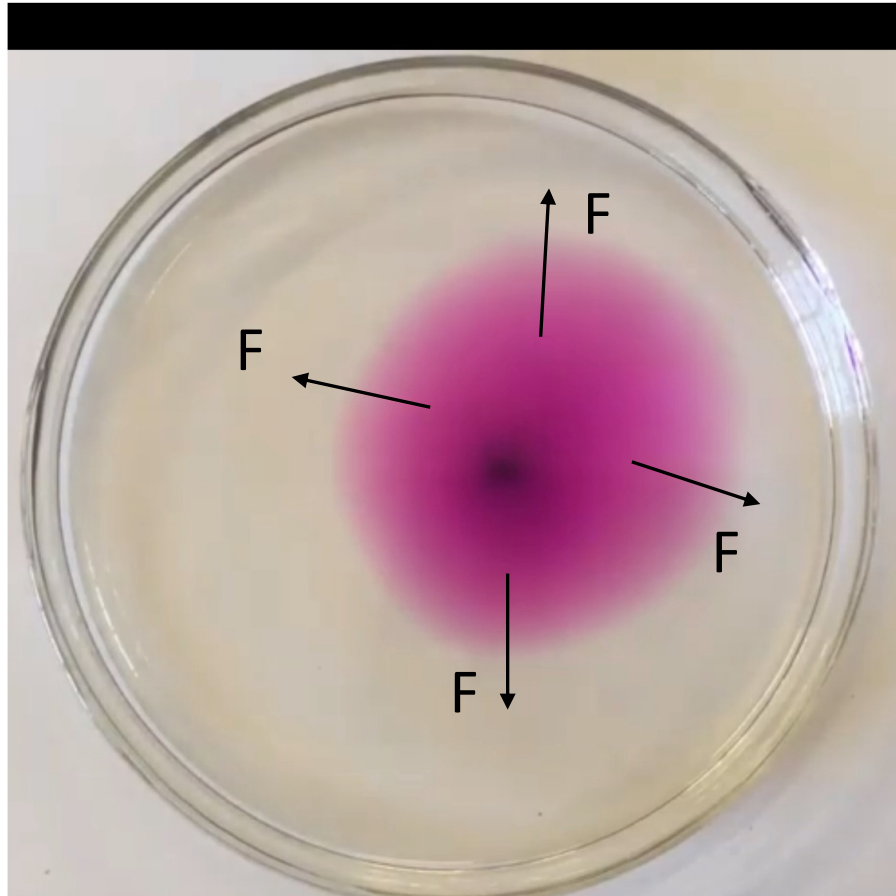
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## 5.2 Carrier diffusion

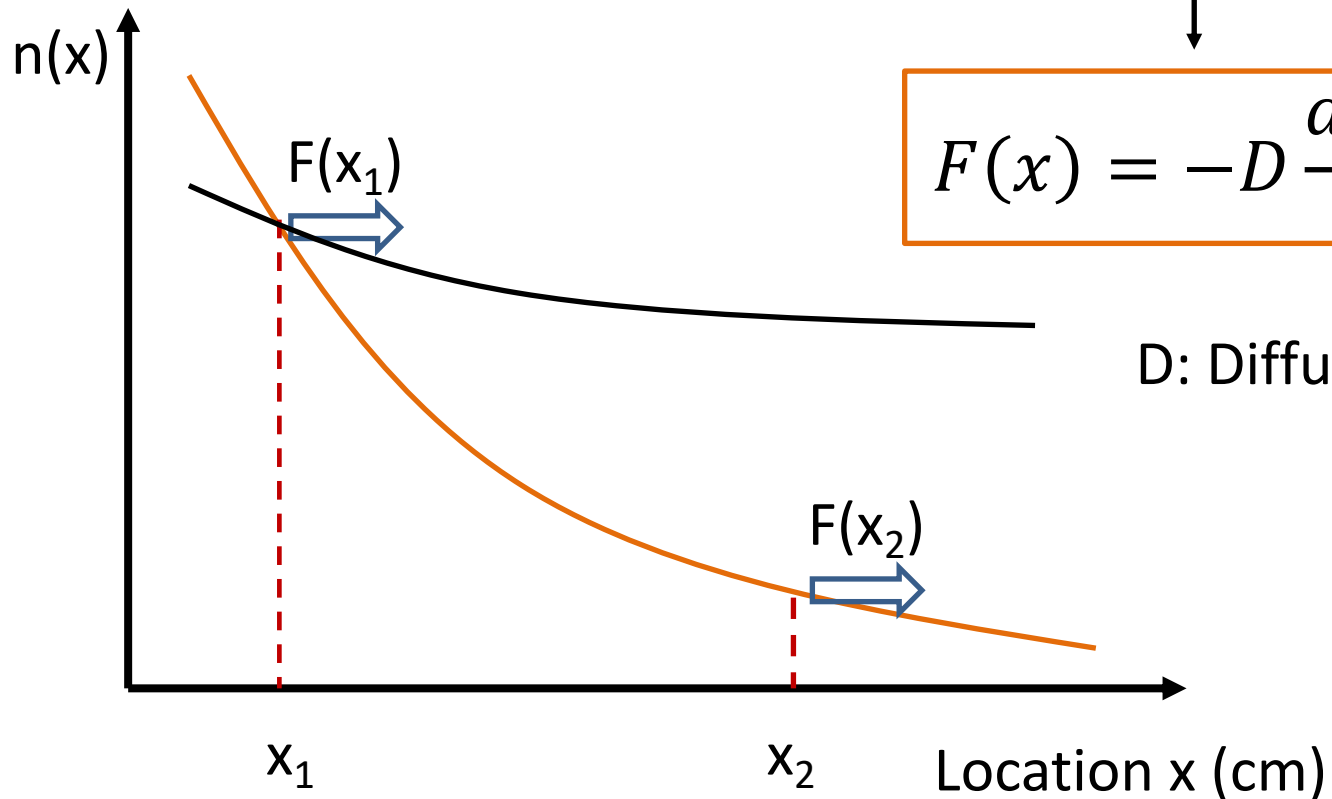
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Flux  $F$ : number of particles passing through a unit area per second

## 5.2 Carrier diffusion

Particle concentration  $n$  ( $\text{cm}^{-3}$ )



$$F(x) \sim \frac{dn(x)}{dx}$$



$$F(x) = -D \frac{dn(x)}{dx}$$

$D$ : Diffusivity

## 5.2 Carrier diffusion

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### Diffusion current density

Electron diffusion current density:  $J_{nx|dif} = -qF_n = qD_n \frac{dn}{dx}$

$D_n$  is called the electron diffusion coefficient

Hole diffusion current density:  $J_{px|dif} = qF_p = -qD_p \frac{dp}{dx}$

$D_p$  is called the hole diffusion coefficient

## 5.2 Carrier diffusion

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### Total current density

$$J = J_{drf} + J_{dif} = J_{n|drf} + J_{p|drf} + J_{n|dif} + J_{p|dif}$$

$$= qn\mu_n E_x + qp\mu_p E_x + qD_n \frac{dn}{dx} - qD_p \frac{dp}{dx}$$

$$J = qn\mu_n E_x + qp\mu_p E_x + qD_n \nabla n - qD_p \nabla p$$

## 5.2 Carrier diffusion

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### Problem Example #2

The hole density in silicon is given by  $p(x) = 10^{16} \exp(-x/L_p)$  ( $x \geq 0$ ) where  $L_p = 2 \times 10^{-4}$  cm. Assume the hole diffusion coefficient is  $D_p = 8 \text{ cm}^2/\text{s}$ . Determine the hole current density at  $x = 2 \times 10^{-4}$  cm.

$$J_{p|diff} = -qD_p \frac{dp}{dx}$$

# Outline

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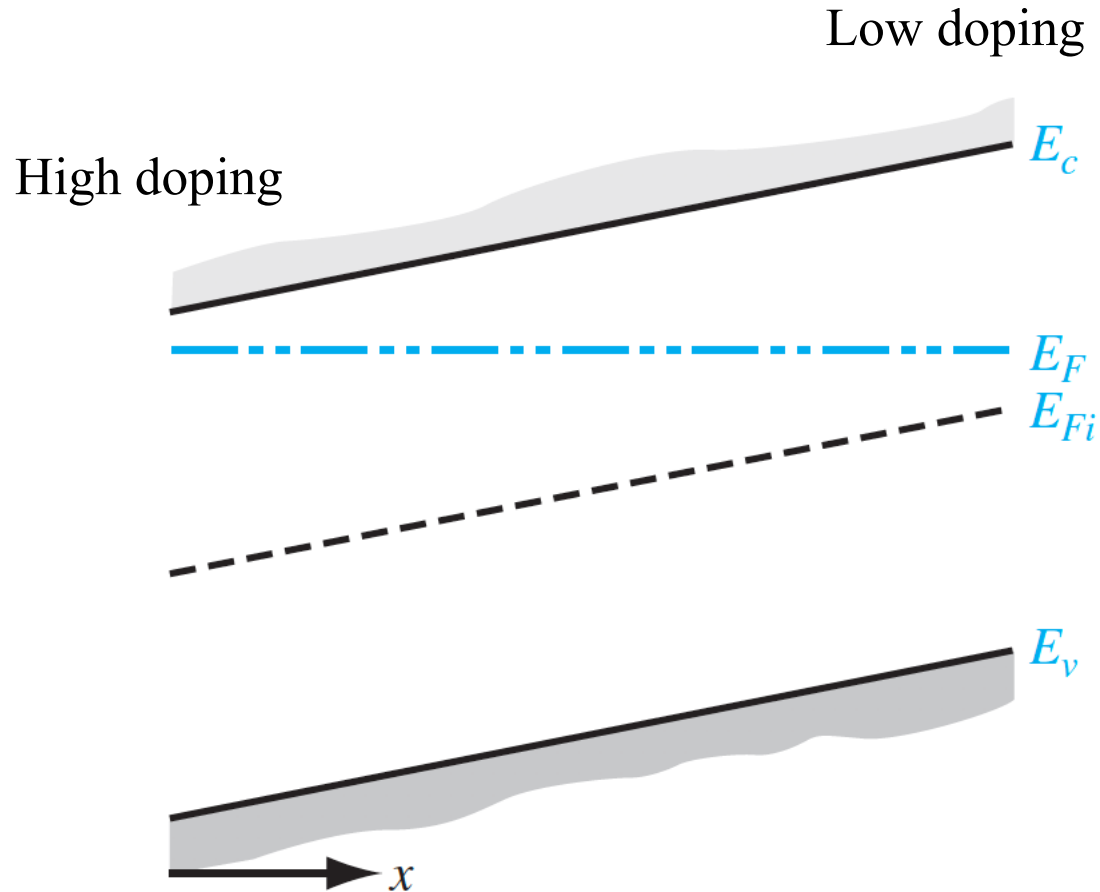
5.1 Carrier drift

5.2 Carrier diffusion

**5.3 Graded impurity distribution**

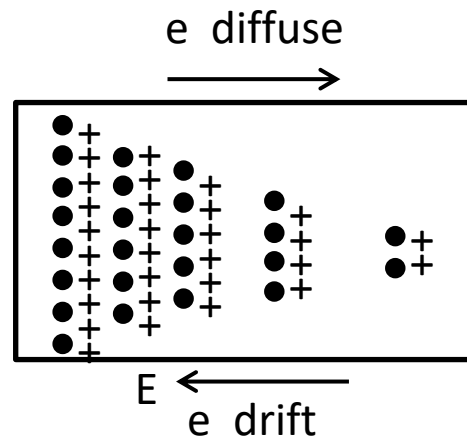
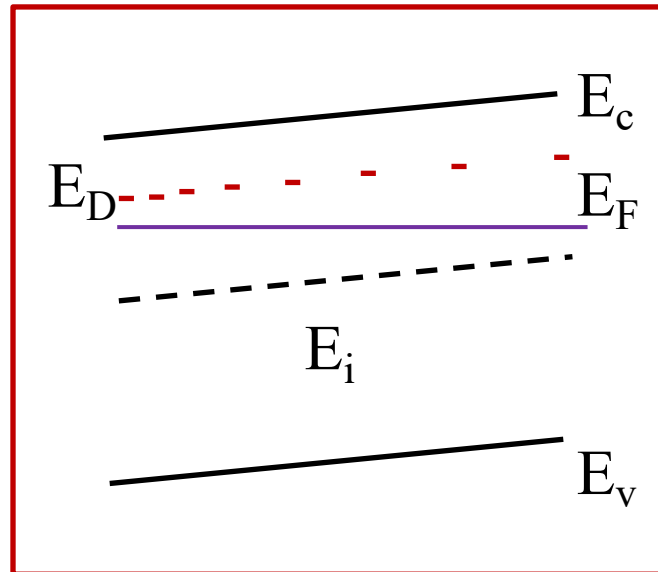
## 5.3 Graded impurity distribution

### Induced electric field



## 5.3 Graded impurity distribution

- Induced electric field



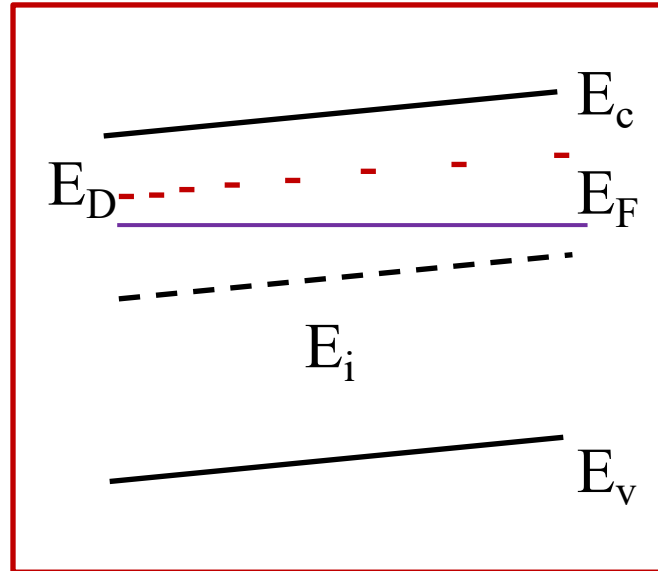


## 5.3 Graded impurity distribution

- The Einstein relation

$$E_x = -\frac{d\phi}{dx} = \frac{1}{q} \frac{dE_i}{dx}$$

$$= \frac{1}{q} \frac{kT}{n(x)} \frac{dn(x)}{dx}$$



$$\phi = \frac{1}{q} (E_F - E_i)$$

$$E_x = -\frac{d\phi}{dx} = \frac{1}{q} \frac{dE_i}{dx}$$

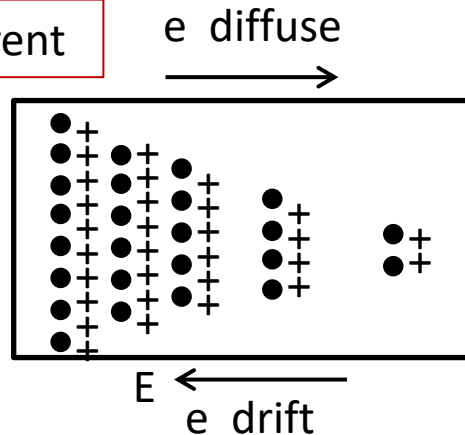
$$n = n_i \exp\left(\frac{E_F - E_i}{kT}\right)$$

$$E_F - E_i = kT \ln(n/n_i)$$

Drift current = diffusion current

$$J_{n,drift} = qn(x)\mu_n|E|$$

$$J_{n,diff} = qD_n \frac{dn(x)}{dx}$$



## 5.3 Graded impurity distribution

- The Einstein relation

$$J_{n,drift} = qn(x)\mu_n|E| = qD_n \frac{dn(x)}{dx} = J_{n,diff}$$

$$qn(x)\mu_n \left( \frac{1}{q} \frac{kT}{n(x)} \frac{dn(x)}{dx} \right) = qD_n \frac{dn(x)}{dx}$$

$$\cancel{qn(x)\mu_n} \left( \cancel{\frac{1}{q}} \cancel{\frac{kT}{n(x)}} \cancel{\frac{dn(x)}{dx}} \right) = \cancel{qD_n} \cancel{\frac{dn(x)}{dx}}$$

$$E_x = -\frac{d\phi}{dx} = \frac{1}{e} \frac{dE_i}{dx}$$

$$= \frac{1}{q} \frac{kT}{n(x)} \frac{dn(x)}{dx}$$

$$D_n = \frac{\mu_n kT}{q}$$

# Check your understanding

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## Problem Example #3

Assume the donor concentration in an n-type semiconductor at  $T = 300\text{K}$  is given by  $N_d(x) = 10^{16}\exp(-x/L)$  where  $L = 2 \times 10^{-2} \text{ cm}$ . Determine the induced electric field and drift current density in the semiconductor at  $x = 2 \times 10^{-2} \text{ cm}$ . Note  $\mu_n \approx 1350 \text{ cm}^2/\text{Vs}$  and  $1200 \text{ cm}^2/\text{Vs}$  near the doping concentration of  $3.68 \times 10^{15} \text{ cm}^{-3}$  and  $10^{16} \text{ cm}^{-3}$ , respectively.

$$E_x = -\frac{1}{q} \frac{kT}{n(x)} \frac{dn(x)}{dx}$$